A METHOD FOR PLASMA ETCHING PERFORMANCE ENHANCEMENT

ABSTRACT OF THE DISCLOSURE

A method for etching a feature in a layer through an etching mask is provided. A protective layer is formed on exposed surfaces of the etching mask and vertical sidewalls of the feature with a passivation gas mixture. The feature is etched through the etching mask with reactive etching mixtures containing at least one etching chemical and at least one passivation chemical.

Fig.3